



Lecture 2: Moore's Law Lecture 3: Semiconductor Economics What are the current Moore's Law doubling What are the three versions of Moore's rates for logic and flash? Law? What is the fundamental economic principle What is Dennard scaling? of Moore's Law? What are three ways manufacturers have Why does Dennard scaling no longer been able to lower the cost per transistor? work? How do lithography costs scale with wafer What are the consequences of the end of size? Dennard scaling? Why is Moore's Law getting harder to keep going? © Chris Mack, 2013 © Chris Mack, 2013

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Lecture 4: Single-Crystal Silicon

- Describe the Czochrolski growth process
- Why do Goup IV materials often act as semiconductors?
- Define "intrinsic semiconductor"
- Explain the processes of electron-hole generation and recombination
- What are the two charge carriers in semiconductor devices?

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Lecture 5: Doping

- Define "extrinsic silicon"
- · What are donors and acceptors?
- Why must the impurities be incorporated into the crystal lattice before they can act as dopants?
- Understand how to use charge balance and mass action equations to determine *n* and *p* for different doping levels
- Know how to calculate the conductivity of a semiconductor, and the resistance of a bar

Exam #1 Review

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What is drift current? Diffusion current? Define "depletion region" (space charge region) Why does a p-n junction form a depletion region? Why does a p-n junction have a built-in voltage?

• Be able to calculate the p-n junction built-in voltage and depletion width

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Lecture 7: The Junction Diode

- How does bias affect depletion width?
- What is a diode?
- Why does a p-n junction act like a diode
- · Be able to use the diode equation
- Be able to use the C(V) equation

Lecture 8: Transistors When and why are bipolar transistors used in circuits? Describe the basic operation of an nMOS and a pMOS transistor What is an inversion layer?

- Define threshold voltage for MOS transistors
- What is the advantage of CMOS circuits for logic?

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Lecture 9: CMOS Process Flow

- Be able to list the basic steps in the CMOS process flow
- Given a list of processes steps, put them in the correct order
- Be able to find the transistors when looking at a top-down design view

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Lecture 10: Thermal Oxidation, part 1

- What is oxide used for in a CMOS process?
- What are the advantages of thermal oxidation?
- Explain the basic workings of an oxidation furnace
- Why is HCI used in the oxidation process?
- How does one insure good oxide thickness uniformity?

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Lecture 11: Thermal Oxidation, part 2

- What are the three sequential steps in the Deal-Grove mechanism?
- What are the limitations of the Deal-Grove model?
- Explain the steady-state assumption used in the derivation
- Be familiar with the derivation of the Deal-Grove model

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Lecture 12: Thermal Oxidation, part 3 Be able to make calculations using the Deal-Grove model What are the linear and parabolic rate constants? Understand how to use τ when an initial oxide film is on the wafer - Understand why $\boldsymbol{\tau}$ is used for dry oxidation

- calculations for film thickness > 30 nm How does pressure affect oxidation rates?
- · How does crystal orientation affect oxidation rates?

Lecture 13: Diffusion, part 1

- What are the two meanings of the term 'diffusion' in semiconductor processing?
- Explain how dopants are introduced during an old-style diffusion step
- Why is dopant diffusion inevitable after ion implantation?
- What does one need to know in order to solve the diffusion equation?

Lecture 14: Diffusion, part 2 Lecture 15: Diffusion, part 3 · What are the cases where we have How does charge in a vacancy affect diffusivity? derived simple analytical solutions to the What is the main cause of the concentration diffusion equation? dependence of the diffusivity of dopants in silicon? What assumptions did we have to make in Define 'transient-enhanced diffusion' order to derive our solutions? · What is electric field enhancement of When might these solutions be useful? diffusivity? Explain how the overall thermal budget for dopant diffusion is accounted for © Chris Mack, 2013

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Lecture 16: Ion Implantation, part 1

- What are the three major process parameters for ion implantation?
- How many CMOS process steps can you name that use ion implantation?
- Describe how a mass spectrometer (mass analyzer) works
- How is dose controlled?

Lecture 17: Ion Implantation, part 2

- What processes affect the trajectory of an ion through a wafer?
- Explain Monte Carlo simulations of ion implantation.
- What are the parameters used in the Gaussian model of implant distribution?
- Define 'straggle' and 'transverse straggle'.

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Lecture 18: Ion Implantation, part 3

- How and why does channeling occur?
- What is the most common remedy for channeling?
- Explain shadowing and how it is mitigated
- What is required of an implant mask?
- How is implant damage repaired?

Why are shallow junctions needed today, and why are they hard to make?
Describe the basic components of an RTP system?
How is heating accomplished in an RTP system?
How is temperature measured in an RTP system?

• What is RTP used for?

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